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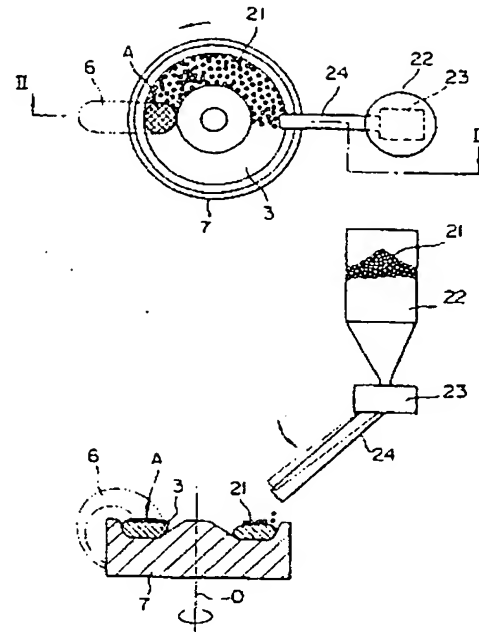
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TITLE : METHOD FOR SUPPLYING MATERIAL
FOR VAPOR DEPOSITION OF VAPOR
SOURCE



ABSTRACT : PURPOSE: To maintain the initial shape of a material for vapor deposition and to form a uniform and good film by evaporating the material for vapor deposition while shifting the melting part thereof continuously on a prescribed locus and by replenishing the granular bodies of the material for vapor deposition to the position evading the melting part.

CONSTITUTION: A crucible 7 contg. the material 3 for vapor deposition for plating molded to a doughnut shape is rotated around an axial line O in a vacuum chamber of a vapor deposition plating device. The above-mentioned material 3 for vapor deposition is melted by an electron beam. The material A for vapor deposition is deposited by evaporation from the melting part A of the material 3 for vapor deposition while said melting part A is shifted continuously along the circular orbit, by which said material is deposited on a substrate (not shown) and the film is formed. The granular bodies 21 of the material for vapor deposition are supplied from a storage hopper 22 via a feeding device 23 and a charging chute 24 to the position of the material 3 for vapor deposition evading the melting part A at the present point of the time on the locus where the above-mentioned melting part A shifts in the above-mentioned vapor source. Further, the granular bodies 21 are continuously replenished by each consumed component by evaporation of the material 3. The initial shape of the material 3 is thereby maintained and the stable operation is attained.

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